

ABSTRACT OF THE DISCLOSURE

A method for manufacturing an electron-emitting device processing an electroconductive film upon which an electron-emission region is formed is characterized
5 in that the formation process of formation of the electron-emission region includes a process of application of metal compound-containing material and film thickness controlling agent to the substrate.

A method for manufacturing an electron source
10 comprises a substrate, and a plurality of electron-emitting devices arrayed upon the substrate, wherein the electron-emitting devices are manufactured according to the method for manufacturing the electron-emitting device.

15 A method for manufacturing an image-forming apparatus comprises a substrate, an electron source comprised of a plurality of electron-emitting devices arrayed upon the substrate, and an image-forming member, wherein the electron-emitting devices are
20 manufactured according to the method for manufacturing an electron-emitting device.